

**WATER AND AQUEOUS BASE SOLUBLE ANTIREFLECTIVE
COATING/HARDMASK MATERIALS**

ABSTRACT OF THE DISCLOSURE

A multilayer lithographic structure which includes a substrate, having on a major surface thereof a first layer including a water and/or aqueous base soluble material which includes Ge, O, and H, and optionally X, wherein X is at least one of Si, N, and F; and disposed on the first layer a second layer which includes an energy photoactive material.